

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	1	(production method adj3 SiC monitor wafer).clm.	US-PGPUB	ADJ	ON	2005/10/13 17:51
L2	1	(depositing SiC adj2 crystal system).clm.	US-PGPUB	ADJ	ON	2005/10/13 17:51
L3	1	(detaching adj2 SiC adj3 substrate).clm.	US-PGPUB	ADJ	ON	2005/10/13 17:52
L4	1	(flattening adj2 SiC surface).clm.	US-PGPUB	ADJ	ON	2005/10/13 17:52
L5	0	(mechanical polishing near combination near CMP).clm.	US-PGPUB	ADJ	ON	2005/10/13 17:54
L6	3	(mechanical polishing near5 combination near5 CMP).clm.	US-PGPUB	ADJ	ON	2005/10/13 17:55
L7	0	(irradiatin adj3 surface adj3 GCIB).clm.	US-PGPUB	ADJ	ON	2005/10/13 17:56
L8	1	(irradiating adj3 surface adj3 GCIB).clm.	US-PGPUB	ADJ	ON	2005/10/13 17:56